

ABSTRACT OF THE DISCLOSURE

An apparatus and method for simulating phenomena of a combined particle formed of substrate particles and adsorbate particles. The simulated phenomena can include, for example, crystal growth, 5 crystal surface adsorption and surface damage. The apparatus includes a kinetic condition setting unit and a particle motion computing unit. The kinetic condition setting unit sets information for defining kinetic conditions of the adsorbate particles. The particle motion computing unit generates the 10 adsorbate particles in accordance with the information set by the kinetic condition setting unit and computes motion of the generated adsorbate particles, to simulate phenomena of the combined particle.